

Electronic Patent Application Fee Transmittal

Application Number:	10827556
Filing Date:	19-Apr-2004
Title of Invention:	PHOTOMASK FOR FORMING PHOTORESIST PATTERNS REPEATING IN TWO DIMENSIONS AND METHOD OF FABRICATING THE SAME
First Named Inventor/Applicant Name:	Chan Hwang
Filer:	Frank Chau
Attorney Docket Number:	8028-43 (SPX200304-0016US)

Filed as Large Entity

Utility Filing Fees

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Basic Filing:				
Pages:				
Claims:				
Miscellaneous-Filing:				
Petition:				
Patent-Appeals-and-Interference:				
Post-Allowance-and-Post-Issuance:				
Utility Appl issue fee	1501	1	1440	1440
Publ. Fee- early, voluntary, or normal	1504	1	300	300

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Extension-of-Time:				
Miscellaneous:				
Printed copy of patent - no color	8001	2	3	6
Total in USD (\$)				1746